

Title (en)

REFLECTIVE MASK BLANK FOR EUV LITHOGRAPHY AND METHOD FOR PRODUCING SAME

Title (de)

REFLEKTIERENDER MASKENROHLING FÜR DIE EUV-LITHOGRAPHIE UND HERSTELLUNGSVERFAHREN DAFÜR

Title (fr)

ÉBAUCHE DE MASQUE RÉFLÉCHISSANT POUR LITHOGRAPHIE EUV ET PROCÉDÉ DE FABRICATION DE LADITE ÉBAUCHE

Publication

**EP 1791168 A1 20070530 (EN)**

Application

**EP 05775172 A 20050829**

Priority

- JP 2005015678 W 20050829
- JP 2004271596 A 20040917

Abstract (en)

A reflective-type mask blank for EUV lithography for reducing the EUV ray reflectance at the absorbing layer and a method for producing the mask blank are presented. A reflective-type mask blank for EUV lithography comprising a substrate and a reflective layer for reflecting EUV light and an absorbing layer for absorbing EUV light, which are formed on the substrate in this order, the reflective-type mask blank for EUV lithography being characterized in that the absorbing layer is a Cr layer of low EUV ray reflectance deposited by an ion beam sputtering method.

IPC 8 full level

**H01L 21/027** (2006.01); **G03F 1/22** (2012.01); **G03F 1/24** (2012.01); **G03F 1/54** (2012.01)

CPC (source: EP KR US)

**B82Y 10/00** (2013.01 - EP KR US); **B82Y 40/00** (2013.01 - EP US); **C03C 17/36** (2013.01 - EP KR US); **C03C 17/3615** (2013.01 - EP KR US); **C03C 17/3639** (2013.01 - EP KR US); **C03C 17/3649** (2013.01 - EP KR US); **C03C 17/3665** (2013.01 - EP KR US); **C23C 14/46** (2013.01 - EP KR US); **G03F 1/22** (2013.01 - EP KR US); **G03F 1/24** (2013.01 - EP KR US); **G03F 1/38** (2013.01 - KR); **G03F 1/54** (2013.01 - EP KR US); **G21K 1/062** (2013.01 - EP US); **C03C 2217/734** (2013.01 - EP US); **C03C 2218/156** (2013.01 - EP US); **C03C 2218/33** (2013.01 - EP US); **G21K 2201/067** (2013.01 - EP US)

Designated contracting state (EPC)

AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IS IT LI LT LU LV MC NL PL PT RO SE SI SK TR

DOCDB simple family (publication)

**US 2006251973 A1 20061109**; EP 1791168 A1 20070530; JP WO2006030627 A1 20080508; KR 20070054651 A 20070529; TW 200622508 A 20060701; WO 2006030627 A1 20060323

DOCDB simple family (application)

**US 40186306 A 20060412**; EP 05775172 A 20050829; JP 2005015678 W 20050829; JP 2006535122 A 20050829; KR 20077005529 A 20070308; TW 94131360 A 20050912